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Seebeck coefficient in multiphase thin films

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ABSTRACT

Mg-Ag-Sb thin films were deposited by magnetron sputtering using a commercial $\text{Mg}_{1/3}\text{Ag}_{1/3}\text{Sb}_{1/3}$ target. All the films contain principally the two phases Ag_3Sb and $\alpha\text{-MgAgSb}$ in same proportions but exhibit different microstructures. The films have the same Seebeck coefficient despite the difference of interface density and structure. Theoretical calculations show that the film effective Seebeck coefficient S_{film} is depending only on the volume of each phase present in the film and their Seebeck coefficients. The multiple interfaces between the different phases have no effect on S_{film} .

Keywords: Thermoelectricity, Seebeck coefficient, Interface, Thin film, MgAgSb

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Several solutions allowing the production of efficient thermoelectric materials were recently proposed [1]. Among them, charge carrier energy filtering is considered as one of the most promising strategy [1,2]. The principal method consists in the creation of specific interfaces in the material acting as energy filtering barriers, promoting a significant increase of the Seebeck coefficient (S) and of the thermoelectric power factor. Experimental variations of S in materials containing inclusions are regularly attributed to energy filtering. However, when several phases are present in a thermoelectric polycrystalline material, the effective Seebeck coefficient S_{eff} is depending on S_{φ_i} of each present phase φ_i . Assuming a constant temperature (T) gradient in the film, and excluding any interface effects, S_{eff} of a material containing n different phases can be expressed such as:

$$S_{eff} = \sum_i^n f_{\varphi_i} \times S_{\varphi_i} \quad (1)$$

with f_{φ} the volume fraction of the phase φ_i (Fig. 1). In the present work, we investigate the interface influence on the S of a polycrystalline material containing several phases. α -MgAgSb is a ternary semi-conductor [3], which usually contains inclusions of the metallic binary phase Ag₃Sb [3]. The S of α -MgAgSb was reported to significantly vary depending on the fabrication process [4–6]. α -MgAgSb has been to date only studied in its bulk state, but α -MgAgSb thin films produced by sputtering are expected to be useful for the integration of energy harvesting devices in the CMOS technology [7].

Mg-Ag-Sb thin films were deposited in a magnetron sputtering system exhibiting a base pressure of 10^{-8} Torr, using a 99.9999% pure Ar gas flow to sputter in the DC mode a 99.99% pure Mg_{1/3}Ag_{1/3}Sb_{1/3} target purchased from CODEX international. The films were deposited on glass substrates for S measurements, or on the native oxide of Si(001) substrates

for electron microscopy observations. Four 300 nm-thick Mg-Ag-Sb films were deposited. Two films were deposited at room temperature (RT), the first one (#1) was kept as-deposited, while the second one (#2) was ex situ annealed under vacuum (10^{-7} mbar) at 523 K for 30 min. The two other films were deposited at 523 K (#3) and 573 K (#4), respectively. The structure of the films was investigated using X-ray diffraction (XRD) in the Bragg-Brentano (θ - 2θ) geometry using a Cu K_α source ($\lambda_{K\alpha} = 0.154$ nm), as well as using scanning electron microscopy (SEM) in cross-section. The S of the films was measured using a home-made setup. T and the electrical potential were measured with the same probes at two different locations on the specimens separated by 1 cm. S was measured between $T = 220$ and 330 K, corresponding to the temperature range of the targeted CMOS applications. The experimental S were compared to theory, running the BoltzTraP code [8] with material bulk parameters determined from ab-initio calculations. Ab-initio calculations were carried out using the first-principles pseudopotential method based on the DFT and the plane-wave self-consistent field method (PWSCF) which is implemented in the QUANTUM ESPRESSO package [9]. The Generalized Gradient Approximation (GGA-PBE) [10] was used for exchange-correlation functional. The ultrasoft pseudopotential (USP) method was used to treat the valence electron configuration.

Figure 2 presents the X-ray diffractograms measured on the four specimens. Fig. 2a shows that only the binary phase Ag_3Sb is detected in the film after deposition at RT. Seven diffraction peaks are detected corresponding to the Ag_3Sb atomic planes (110), (002), (111), (022), (130), (023), and (132) at $2\theta = 34.32^\circ$, 37.24° , 39.23° , 51.56° , 61.77° , 68.44° , and 74.29° , respectively. Fig. 2b shows that annealing the same film at 523 K for 30 min allows the phase $\alpha\text{-MgAgSb}$ as well as the phase Sb to form in the film in addition to the phase Ag_3Sb . In addition to the same Ag_3Sb diffraction peaks, five diffraction peaks corresponding

to α -MgAgSb(110), α -MgAgSb(202), α -MgAgSb(114), α -MgAgSb(330), and α -MgAgSb(006) are respectively observed in the diffractogram at $2\theta = 13.01^\circ$, 24.16° , 31.88° , 41.25° , and 42.06° , as well as two peaks corresponding to Sb(102) and Sb(213) at $2\theta = 28.69^\circ$ and 48.35° . Fig. 2c and Fig. 2d show that the same diffraction peaks are observed in the samples heated at 523 K or 573 K during deposition. Only the peak $\text{Ag}_3\text{Sb}(130)$ is only observed in the specimen ex situ annealed. The (qualitative) volume fraction f of each phase present in the different films was determined using the integration of each detected peak of each phase. Due to the uncertainties related to the Bragg-Brentano geometry, the values of f should not be considered quantitatively. Nevertheless, the fractions corresponding to the three phases present in the films are the same in the three different films #2, #3, and #4: $f_\alpha \sim 33\%$, $f_{\text{Ag}_3\text{Sb}} \sim 60\%$, and $f_{\text{Sb}} \sim 7\%$. Fig. 3 presents cross-sectional SEM images obtained on the films #1 (Fig. 3a), #2 (Fig. 3b), #3 (Fig. 3c), and #4 (Fig. 3d). The SEM images show in the four films the coexistence of multiple grains of different phases exhibiting different contrasts. However, the microstructures of the samples #2, #3, and #4 are different. According to the XRD analyses, the matrix should correspond to the phase Ag_3Sb , while the inclusions should be α -MgAgSb grains. The inclusions in the film #2 exhibit a higher density ($\rho \sim 1.5 \times 10^{11} \text{ cm}^{-2}$) and smaller sizes ($10 \leq l \leq 50 \text{ nm}$) than in the film #3 ($\rho \sim 8.2 \times 10^9 \text{ cm}^{-2}$, $23 \leq l \leq 70 \text{ nm}$) and #4 ($\rho \sim 3.5 \times 10^9 \text{ cm}^{-2}$, $65 \leq l \leq 90 \text{ nm}$). Furthermore, the film #3 is rougher and facets are less easily observed on the inclusions compared to film #4. Fig. 4 presents S measured on the four different films versus T . S measured on the films #2 (open up triangles), #3 (solid circles), and #4 (solid squares), are similar in the considered T range. However, S measured on the as-deposited film #1 (solid down triangles) is significantly lower than the three other films. Indeed, S measured in the film #1 should correspond to the phase Ag_3Sb , while S measured on the three other films should correspond to an effective coefficient resulting from the presence of the different phases. Fig. 4 shows also the theoretical S of the

two major phases present in the samples (i.e. Ag_3Sb and $\alpha\text{-MgAgSb}$) calculated using the BoltzTraP code and ab-initio calculations. The theoretical coefficient of Ag_3Sb (solid line) is in good agreement with the experimental coefficient measured on the film #1 (solid down triangles), containing only Ag_3Sb . Furthermore, the theoretical coefficient of $\alpha\text{-MgAgSb}$ is in good agreement with the experimental value reported by Kirkham et al. [4] (solid diamonds). XRD measurements suggest that the phase $\alpha\text{-MgAgSb}$ occupies in average only 30% of the volume of the films #2, #3, and #4. Neglecting the presence of Sb in the samples, S_{eff} of a hypothetic film containing the two phases Ag_3Sb and $\alpha\text{-MgAgSb}$ was calculated using the theoretical values of $S_{\text{Ag}_3\text{Sb}}$ and S_α and eq. 1, with $f_\alpha = 0.3$ and $f_{\text{Ag}_3\text{Sb}} = 0.7$. S_{eff} (dash line in Fig. 4) is in good agreement with the S measured on the three films #2, #3, and #4. Neither nano-size effect [11-12] nor interfacial effect [1-2] are observed on S . Indeed, the microstructures of the films may be too far from the structure of superlattice-type materials, the size of $\alpha\text{-MgAgSb}$ inclusions being too large ($> 5 \text{ nm}$ [11-12]) and exhibiting a significant size distribution. Furthermore, the nature of the $\text{Ag}_3\text{Sb}/\alpha\text{-MgAgSb}$ interface may not promote the suitable energy barrier (ohmic instead of Schottky contact).

In conclusion, Mg-Ag-Sb thin films were elaborated by magnetron sputtering in different conditions allowing the production of different films containing principally the phase Ag_3Sb and the phase $\alpha\text{-MgAgSb}$ in same proportions. These films exhibit the same S_{eff} despite a significant difference of interface density and structure. S_{eff} can be determined considering the Seebeck coefficients of the two different phases and their volume in the films, without considering any influence of the interfaces.

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CAPTIONS

FIG. 1. Schematic showing the serial electrical circuit corresponding to the case of a thermoelectric material made of two different phases $\varphi 1$ and $\varphi 2$ in a temperature gradient, $S_{\varphi 1}$ (resp. $S_{\varphi 2}$) and $\sigma_{\varphi 1}$ (resp. $\sigma_{\varphi 2}$) being the Seebeck coefficient and the electrical conductivity of the phase $\varphi 1$ (resp. $\varphi 2$). Any $\varphi 1/\varphi 2$ interface effect is neglected.

FIG. 2. Ex situ X-ray diffractograms acquired in the θ - 2θ geometry on the four different films: #1 (a), #2 (b), #3 (c), and #4 (d).

FIG. 3. Cross-sectional SEM images acquired on the four different films: a) RT as-deposited film (film #1), b) RT deposited film annealed under vacuum at 523 K for 30 min (film #2), c) film deposited at 523 K (film #3), and d) film deposited at 573 K (film #4).

FIG. 4. Comparison between experimental (solid symbols) and calculated (lines) Seebeck coefficients (S) for $220 \leq T \leq 330$ K: The solid down triangles, the solid circles, and the solid squares correspond to the RT as-deposited film (film #1), the film deposited at 523 K (film #3), and the film deposited at 573 K (film #4). The open up triangles corresponds to the RT deposited film annealed under vacuum at 523 K for 30 min (film #2) and the solid diamonds corresponds to the phase α -MgAgSb from [4]. The lines correspond to the S theoretical values of bulk Ag_3Sb (solid line), bulk α -MgAgSb (dash dot line), and a film containing in its volume 70% of Ag_3Sb and 30% of α -MgAgSb, neglecting $\text{Ag}_3\text{Sb}/\alpha$ -MgAgSb interface effects (dash line).

Figure 1

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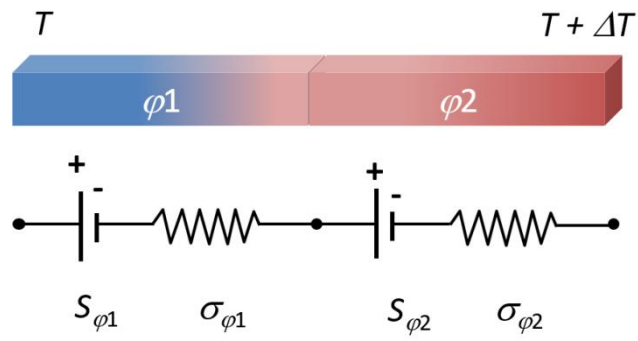


Figure 2

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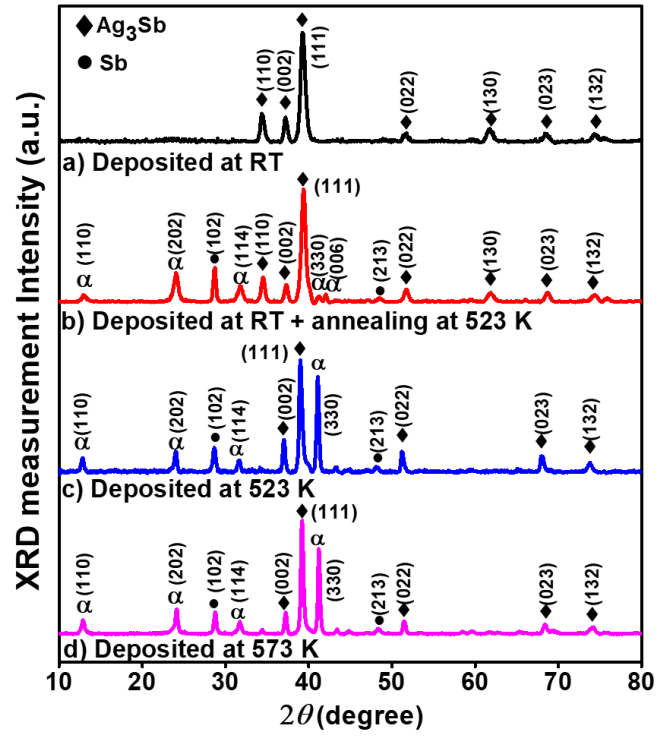


Figure 3

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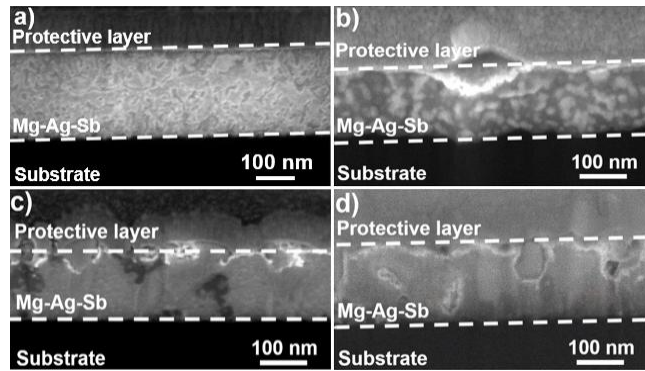


Figure 4

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